

Product Identification

Film Name: PECVD Standard Oxide
 Process ID: D01POX
 Scientific: Silicon Dioxide - SiO2
 Classification: Standard

Features

Low Cost
 Variable Processing Parameters
 Large Batch Capacity
 Low Temperature - Widely Variable
 Custom Fixturing Available

Standards & Guarantees

Inspection: Standard I/O - First & Last
 Guaranteed: Thickness (On Si Monitors)
 Guaranteed: Refractive Index (On Si Monitors)

Items may vary when ordering outside the standard

Applications

Passivation
 Thick Structures
 Insulation Layer
 Inter-layer Dielectric
 Encapsulation
 Patterning
 Masking
 Adhesion Layer
 Barrier Layer

Film Specifications

Film Thickness	Standard	1000A to 10,000A ± 10%
	Adjustable Range	500A to 50,000A ± 10%
Refractive Index	Standard	1.55 ± .05
	Adjustable Range	Fixed
Film Uniformity	Edge to Edge	10%
	Across Load	10%
Deposition Temp	Standard	380C
	Adjustable Range	100C to 600C
Film Stress	Standard	- 200MPa ± 50MPa
	Adjustable Range	Fixed

Film Properties

Electrical	Insulating Quality	Very Good
	Dielectric Constant	N/A
Mechanical	Hydrogen Inclusion	Moderate
	Scratch Protect	Good
	Masking Ability	Good
	Diffusion Barrier	Moderate
	Thermal Stability	Good
Etch Rate	BOE (50%)	Fast
	KOH	N/A
	Plasma	Moderate
Hydrology	Hydrophobic	Moderate